

<b>Notice of References Cited</b>	Application/Control No. 10/720,838	Applicant(s)/Patent Under Reexamination GROS-JEAN ET AL.	
	Examiner B. Chen	Art Unit 1762	Page 1 of 1

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*	C	US-6,552,209 B1	04-2003	Lei et al.	556/42
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**NON-PATENT DOCUMENTS**

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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.